

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments	Error Definition	Errors
1	BRS	L1	0	(substrate\$1 or wafer\$1) with (HF or "HF" or (hydrogen adj fluoride) or hydrofluor\$4) with oxidant\$1 with (solvent\$1 or alcohol\$1 or glycol\$1 or non-protic\$1 or (non adj protic\$1))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 12:34			0
2	BRS	L3	0	(substrate\$1 or wafer\$1) with (HF or "HF" or (hydrogen adj fluoride) or hydrofluor\$4 or hydro-fluor\$4) with oxidant\$1 with (solvent\$1 or alcohol\$1 or glycol\$1 or non-protic\$1 or (non adj protic\$1))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 12:34			0
3	BRS	L2	1	(substrate\$1 or wafer\$1) same (HF or "HF" or (hydrogen adj fluoride) or hydrofluor\$4 or hydro-fluor\$4) same oxidant\$1 same (solvent\$1 or alcohol\$1 or glycol\$1 or non-protic\$1 or (non adj protic\$1))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 13:59			0
4	BRS	L4	86	(convert\$3 or chang\$3 or adapt\$3 or alter\$3 or renovat\$3 or switch\$3 or translat\$3) with (non-porous\$2 or (non adj porous\$2)) with porous\$2 with (silicon or wafer\$1 or substrate)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 13:47			0

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments	Error Definition	Errors
5	BRS	L5	151723	(wafer\$1 or substrate\$1) with (photoresist\$3 or photo-resist\$3 or (photo adj resist\$3) or PR or resist\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 12:48			0
6	BRS	L6	22	4 and 5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 12:50			0
7	BRS	L7	15390	(oxide\$1 or dioxide\$1 or dielectric or insulat\$4) with (varying or variable or varies or vary or differen\$4) with thickness\$2	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 12:54			0
8	BRS	L8	0	6 and 7	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 12:54			0
9	BRS	L9	2	4 and 7	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 12:55			0
10	BRS	L10	5618	first with second with thickness\$2 with (oxide\$1 or dioxide\$1 or dielectric\$1 or insulat\$4) with (smaller or thinner or thin\$4 or thick\$3 or greater or less or more or bigger)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 13:47			0

Type	L #	Hits	Search Text	DBs	Time Stamp	Comments	Error Definition	Errors
11 BRS	L11	306	(convert\$3 or chang\$3 or adapt\$3 or alter\$3 or renovat\$3 or switch\$3 or translat\$3) same (non-porous\$2 or (non adj porous\$2)) same porous\$2 same (silicon or wafer\$1 or substrate)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 13:49			0
12 BRS	L12	61253	(oxidation or oxidizing or oxidized or oxidiz\$8 or oxidat\$4) with (substrate\$1 or wafer\$1)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 14:22			0
13 BRS	L13	19701	7 or 10	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 13:53			0
14 BRS	L14	9	11 and 12 and 13	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 13:54			0
15 BRS	L15	6	14 and 5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 13:55			0
16 BRS	L16	271	(substrate\$1 or wafer\$1) same (HF or "HF" or (hydrogen adj fluoride) or hydrofluor\$4 or hydro-fluor\$4) same (current\$3 or amp\$1 or milli-amp\$1 or (milli adj amp\$1)) same (immers\$4 or dip\$4 or submerg\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 14:49			0

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments	Error Definition	Errors
17	BRS	L17	0	15 and 16	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 14:04			0
18	BRS	L18	1325	(substrate\$1 or wafer\$1) same (HF or "HF" or (hydrogen adj fluoride) or hydrofluor\$4 or hydro-fluor\$4) same (current\$3 or amp\$1 or milli-amp\$1 or (milli adj amp\$1))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 14:07			0
19	BRS	L19	3	15 and 18	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 14:07			0
20	BRS	L20	5551	(oxidation or oxidizing or oxidized or oxidiz\$8 or oxidat\$4) with (rate or rat\$3) with increas\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 14:40			0
21	BRS	L21	257	13 and 20	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 14:26			0
22	BRS	L22	65	5 and 21 and 12	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 14:27			0

Type	L #	Hits	Search Text	DBs	Time Stamp	Comments	Error Definition	Errors
23 BRS	L23	8512	(oxidation or oxidizing or oxidized or oxidiz\$8 or oxidat\$4) with (rate or rat\$3) with (increas\$4 or higher or boost\$3 or enlarg\$3 or rais\$3 or enhanc\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 14:42			0
24 BRS	L24	393	13 and 23	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 14:44			0
25 BRS	L25	108	5 and 12 and 24	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 14:45			0
26 BRS	L26	2115	(substrate\$1 or wafer\$1) same (solution\$1 or solvent\$1) same (current\$3 or amp\$1 or milli-amp\$1 or (milli adj amp\$1)) same (immers\$4 or dip\$4 or submerg\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 14:51			0
27 BRS	L27	2	25 and 26	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 14:52			0
28 BRS	L28	10	24 and 26	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 14:53			0

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments	Error Definition	Errors
29	BRS	L29	0	25 and 2	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 14:54			0
30	BRS	L30	0	24 and 2	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 14:53			0
31	BRS	L31	0	25 and 4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 14:56			0
32	BRS	L32	0	24 and 4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 14:55			0
33	BRS	L33	3	25 and 11	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 14:57			0
34	BRS	L34	3	24 and 11	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 14:56			0
35	BRS	L35	0	25 and 16	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 14:57			0

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments	Error Definition	Errors
36	BRS	L36	1	24 and 16	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 14:57			0
37	BRS	L37	3	24 and 18	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 14:58			0
38	BRS	L38	0	25 and 18	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 14:58			0
39	BRS	L39	69932	STI\$1 or (shallow adj trench adj isolat\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 15:19			0
40	BRS	L40	18	25 and 39	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 15:20			0
41	BRS	L41	5576	(oxide\$1 or dioxide\$1) with porous with (silicon or substrate\$1 or wafer\$1)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 15:22			0
42	BRS	L42	10	25 and 41	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 16:38			0

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments	Error Definition	Errors
43	BRS	L43	436	(oxide\$1 or dioxide\$1) with (nonporous or non-porous or (non adj porous)) with (silicon or substrate\$1 or wafer\$1)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 15:23			0
44	BRS	L44	0	25 and 43	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 15:24			0
45	BRS	L45	0	24 and 43	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/08/04 15:24			0
46	IS&R	L46	289	(438/981).CCLS.	USPAT; US-PGPUB	2002/08/04 16:40			0
47	IS&R	L47	3147	((438/197) or (438/200) or (438/241) or (438/258) or (438/275) or (438/279) or (438/286) or (438/287) or (438/409) or (438/422) or (438/585)).CCLS.	USPAT; US-PGPUB	2002/08/04 16:47			0
48	BRS	L48	547	13 and 47	USPAT; US-PGPUB	2002/08/04 16:48			0